

EIPBN 2016 - Symposium on Lithography and Nanofabrication

Veranstaltung - EIPBN 2016 - Symposium on Lithography and Nanofabrication

Titel	EIPBN 2016 - Symposium on Lithography and Nanofabrication
Wann	Di, 31. Mai 2016 - Fr, 3. Juni 2016

Beschreibung

EIPBN 2016 - Symposium on Lithography and Nanofabrication

The 60th International Conference on Electron, Ion, and Photon Beam Technology and Nanofabrication - the EIPBN, or the “3-Beams”, Conference, is the conference on the science and technology of nanopatterning. Traditionally focused on electron, ion, and photon beams, (the 3 beams), the technology of nano-fabrication covered in this conference has grown to include topics such as nano-imprinting, molecular self-assembly, focused beam processing, and the application of these techniques to create new types of devices. This conference is the place to hear about the newest techniques and the latest advances in patterning and device fabrication technology.

The conference brings together engineers and scientists from industries and universities from all over the world to report on and discuss recent progress and future trends.

Abstracts representing original research are invited in the following areas:

Micro- and Nanolithography

- Electron and Ion beam lithography
- Optical and Extreme UV (EUV) lithography
- Nano-imprint lithography
- Maskless and high throughput direct write lithography
- 3D micro and nanolithography
- Resists and lithographic support materials
- Mask, template and stencil fabrication
- Directed self-assembly
- Tip-based and scanning probe lithography
- Electron and Ion beam sources and optics
- Large area nanoscale patterning
- Simulation and modeling of patterning technologies
- Lithography for packaging and 3D integration

Process and Metrology Technologies

- Electron, ion and photon beam stimulated etching and deposition
- Ion beam microscopy including Ga, He, Li and novel sources
- Multibeam and high throughput imaging instruments
- Nanoparticle and nanotube assembly and placement
- Advanced pattern transfer concepts

- Aberration corrected electron beam instruments
- Process simulation and modeling
- Nanomanipulation and precision placement
- Advanced scanning probe and tip-based imaging
- Processing for novel 2D materials (MoS, graphene)

Applications and Emerging Topics

- Nano-electronics and Bionanoelectronics
- Nano-structured Interfaces to Biology
- Patterned media
- Nano-fabrication for Quantum Computing
- High density solid state storage & nonvolatile memory devices
- Nanophotonics and plasmonics
- Nanobiology and nanomedicine
- Micro- and nanofluidics
- Carbon-based nano-devices (CNTs & graphene)
- Nanofabrication for energy sources
- Micro- and nanoscale mechanical devices and MEMs
- DNA origami and biologically inspired assembly

Learn more by website: www.eipbn.org

Lokalität - Pittsburgh

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